SHEFT 1 OF 1

INFORMATION DISCLOSURE OF ESTATION			CUSTOMER NUMBER 26615		ATTORNEY'S DKT NO. H1130 APPLICANT(S) Bin YU et al. FILING DATE July 8, 2003		APPLICATION No. 10/614,177 GROUP				
PFQ-1449					July 8, 2003		2811				
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).

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APPLICATION NO.

INFORMATION
DISCLOSURE
CITATION
DTO 4440

CUSTOMER

H1130

ATTORNEY'S DKT No.

10/614,177

DISCLOSURE				NUMBER	APPLICANT(S) Bin YU et al.					
CITATION PTO-1449				26615 FILING DATE July 8, 2003			GROUP 2811			
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